

PATENT ATTORNEY DOCKET NO.: 041501-5494

## GROUP TO THE IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Soo Chang CHANG

Application No.: 10/076,097

Filed: February 15, 2002

For: SPUTTERING SYSTEM Confirmation No. 9123

Group Art Unit: 1753

Examiner: R. McDonald

Mail Stop Non-Fee Amendment

Commissioner for Patents U.S. Patent and Trademark Office 2011 South Clark Place Customer Window, Mail Stop Non-Fee Amendment Crystal Plaza Two, Lobby, Room 1B03 Arlington, VA 22202

Sir:

## AMENDMENT

In response to the Office Action mailed March 5, 2003 (Paper No. 5), the period for response to which extends through June 5, 2003, please amend the above-identified application as follows:

## IN THE CLAIMS

Please replace claims 1 and 3-8 with the following:

- 1. (Amended) A sputtering system for depositing a thin film on a substrate, comprising:
  - a vacuum chamber:
  - a support for supporting the substrate in the vacuum chamber;
  - a target arranged to oppose the support;
  - a fixed plate formed on a first side of the target; and

I-WA/1994538.1